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PM  
3/4/03  
XA-9335

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Yutaka SUENAGA et al.

Appln. No.: 09/615,081

Group Art Unit: 2872

Filed: July 12, 2000

Examiner: M. Robinson

For: CATADIORPTIC OPTICAL SYSTEM AND EXPOSURE APPARATUS  
EQUIPPED WITH THE SAME

AMENDMENT ACCOMPANYING REQUEST FOR CONTINUED EXAMINATION

Commissioner for Patents  
Washington, D.C. 20231

Sir:

Prior to continued examination, please amend the above-  
identified patent application as indicated below

03/14/2003 PBRITTON 00000001 09615081

01 FC:1202 IN THE CLAIMS 00 OP  
02 FC:1201 84.00 OP

1 28. (Twice amended) A projection exposure apparatus,  
EI 2 comprising a catadioptric optical system according to Claim  
3 18 which projects a predetermined pattern on a mask onto a  
4 photosensitive substrate.

558.00 OP  
556.00 U

EV 1 40. (Amended) A projection exposure apparatus which  
2 projects a predetermined pattern on a mask onto a

03/14/2003 EBERHARD 00000030 09615081